

## **Remarks/Argument**

### ***Claim Summary***

By this Amendment, claim 1 has been amended, and no other claims have been added to or deleted from the application.

Accordingly, claims 1-37 remain pending in the application.

### ***Restriction/Election***

Claims 12-20, 22 and 24-37 have been withdrawn from consideration.

However, since dependent claims 12-13, 15-17 depend directly or indirectly from claim 1, it is understood that these dependent claims would be allowed upon the eventual allowance of claim 1.

### ***Request For Personal Interview***

The remarks presented below are already of record. However, in an effort to expedite prosecution of the application, Applicants respectfully request that the Examiner grant a personal interview with the undersigned. It is believed that the complexities of the technology associated with the present invention can be better conveyed and analyzed in-person.

The undersigned can be reached at 571.283.0720.

### ***35 U.S.C. ¶102***

Claims 1-3 and 6-11 were variously rejected under 35 U.S.C. ¶102 as being anticipated by Campbell et al. (US 4990229), and/or Maeda et al. (EP 0676793), and/or Boswell (US 4810935), for the reasons stated at pages 3-5 of the Office Action. In each of these rejections, the Examiner states:

“It should be noted that attenuation of the ions which diffuse into the second chamber and approach the workpiece, by directing a proportion of the ions to a loss surface of either chamber will be produced.”

Applicants respectfully disagree with the Examiner’s characterization of the Campbell et al, Maeda et al., and Boswell references.

Attention is directed to the DECLARATION OF DR. LESLIE LEA UNDER 37 C.F.R. ¶1.132 (“the Lea Declaration”) already of record.

As described at paragraph 4 of the Lea Declaration, each of Campbell et al., Maeda et al., and Boswell describe helicon type plasma sources which aim to increase the efficiency of energy transfer from the RF power supply to the plasma, i.e., to increase plasma (ion and electron) density.

Helicon type plasma sources such as those of the cited references achieve a result which is opposite to that attributed by the Examiner, and for at least this reasons, Applicants respectfully traverse the rejections under 35 U.S.C. ¶102.

### **35 U.S.C. ¶103**

Several of the dependent claims were variously rejected under 35 U.S.C. ¶103 as being unpatentable over Campbell et al. or Maeda et al. or Boswell, in combination with various secondary references cited by the Examiner at pages 6-14 of the Office Action. However, Applicants respectfully traverse these rejections for at least the same reasons as stated above in connection the rejections under 35 U.S.C. ¶102.

***Conclusion***

No other issues remaining, reconsideration and favorable action upon the present claims are requested.

Respectfully submitted,

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